

## IN THE CLAIMS

Please amend the claims as follows:

Claim 1. (Original) A method of cleaning a heat treatment apparatus that deposits an SiO<sub>2</sub> film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying an HF gas and an NH<sub>3</sub> gas into the treatment vessel.

Claim 2. (Original) The method of cleaning a heat treatment apparatus according to claim 1, wherein

during the cleaning step, a temperature in the treatment vessel is in a range of from 100°C to 300°C.

Claim 3. (Original) The method of cleaning a heat treatment apparatus according to claim 1 or 2, wherein

during the cleaning step, a pressure in the treatment vessel is equal to or more than 53200 Pa (400 Torr).

Claim 4. (Currently Amended) The method of cleaning a heat treatment apparatus according to ~~any one of claims 1 to 3~~ claim 1 or 2, wherein

during the cleaning step, a supply amount of the HF gas is equal to or more than a supply amount of the NH<sub>3</sub> gas.

Claim 5. (Original) A method of cleaning a heat treatment apparatus that deposits an AsSG film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying an HF gas and an NH<sub>3</sub> gas into the treatment vessel.

Claim 6. (Original) A method of cleaning a heat treatment apparatus that deposits a BSG film by means of TEOS on an object to be processed contained in a treatment vessel capable of forming a vacuum, the method comprising the step of:

cleaning the heat treatment apparatus by supplying an HF gas and an NH<sub>3</sub> gas into the treatment vessel.

Claim 7. (New) The method of cleaning a heat treatment apparatus according to claim 3, wherein

during the cleaning step, a supply amount of the HF gas is equal to or more than a supply amount of the NH<sub>3</sub> gas.